

Kenji Ishikawa

List of Publications by Year in descending order

Source: <https://exaly.com/author-pdf/6361869/publications.pdf>

Version: 2024-02-01

288
papers

5,486
citations

109321

35
h-index

123424

61
g-index

294
all docs

294
docs citations

294
times ranked

3648
citing authors

#	ARTICLE	IF	CITATIONS
1	Enhancement of ethanol production and cell growth in budding yeast by direct irradiation of low-temperature plasma. Japanese Journal of Applied Physics, 2022, 61, SA1007.	1.5	1
2	Functional nitrogen science based on plasma processing: quantum devices, photocatalysts and activation of plant defense and immune systems. Japanese Journal of Applied Physics, 2022, 61, SA0805.	1.5	13
3	Perspectives on functional nitrogen science and plasma-based in situ functionalization. Japanese Journal of Applied Physics, 2022, 61, SA0802.	1.5	6
4	Scaffolds with isolated carbon nanowalls promote osteogenic differentiation through Runt-related transcription factor 2 and osteocalcin gene expression of osteoblast-like cells. AIP Advances, 2022, 12, .	1.3	3
5	Plasma-assisted thermal-cyclic atomic-layer etching of tungsten and control of its selectivity to titanium nitride. Journal of Vacuum Science and Technology B: Nanotechnology and Microelectronics, 2022, 40, 022201.	1.2	1
6	Low-temperature reduction of SnO ₂ by floating wire-assisted medium-pressure H ₂ /Ar plasma. Plasma Processes and Polymers, 2022, 19, .	3.0	3
7	In-liquid plasma synthesis of iron-nitrogen-doped carbon nanoflakes with high catalytic activity. Plasma Processes and Polymers, 2022, 19, .	3.0	3
8	Cytotoxicity of plasma-irradiated lactate solution produced under atmospheric airtight conditions and generation of the methyl amino group. Applied Physics Express, 2022, 15, 056001.	2.4	6
9	Study of optical emission spectroscopy using modified Boltzmann plot in dual-frequency synchronized pulsed capacitively coupled discharges with DC bias at low-pressure in Ar/O ₂ /C ₄ F ₈ plasma etching process. Physical Chemistry Chemical Physics, 2022, 24, 13883-13896.	2.8	5
10	Wide range applications of process plasma diagnostics using vacuum ultraviolet absorption spectroscopy. Reviews of Modern Plasma Physics, 2022, 6, .	4.1	4
11	Selective etching of SiN against SiO ₂ and poly-Si films in hydrofluoroethane chemistry with a mixture of CH ₂ FCH ₂ , O ₂ , and Ar. Applied Surface Science, 2021, 541, 148439.	6.1	17
12	Influences of substrate temperatures on etch rates of PECVD-SiN thin films with a CF ₄ /H ₂ plasma. Applied Surface Science, 2021, 542, 148550.	6.1	20
13	Improvement of yield and grain quality by periodic cold plasma treatment with rice plants in a paddy field. Plasma Processes and Polymers, 2021, 18, .	3.0	35
14	Mechanistic understanding of cold atmospheric plasma applications. Japanese Journal of Applied Physics, 2021, 60, 020401.	1.5	1
15	Impact of seed color and storage time on the radish seed germination and sprout growth in plasma agriculture. Scientific Reports, 2021, 11, 2539.	3.3	28
16	Growth inhibition effect on Trypanosoma brucei gambiense by the oxidative stress supplied from low-temperature plasma at atmospheric pressure. Japanese Journal of Applied Physics, 2021, 60, 020601.	1.5	0
17	Hydrogen peroxide in lactate solutions irradiated by non-equilibrium atmospheric pressure plasma. Plasma Sources Science and Technology, 2021, 30, 04LT03.	3.1	8
18	Cancer Treatments Using Low-Temperature Plasma. Current Medicinal Chemistry, 2021, 28, 8549-8558.	2.4	12

#	ARTICLE	IF	CITATIONS
19	Brain cell proliferation in adult rats after irradiation with nonequilibrium atmospheric pressure plasma. <i>Applied Physics Express</i> , 2021, 14, 067002.	2.4	4
20	Plasma-activated Ringer's lactate solution inhibits the cellular respiratory system in HeLa cells. <i>Plasma Processes and Polymers</i> , 2021, 18, 2100056.	3.0	9
21	Lysosomal nitric oxide determines transition from autophagy to ferroptosis after exposure to plasma-activated Ringer's lactate. <i>Redox Biology</i> , 2021, 43, 101989.	9.0	55
22	Effects of hydrogen content in films on the etching of LPCVD and PECVD SiN films using CF ₄ /H ₂ plasma at different substrate temperatures. <i>Plasma Processes and Polymers</i> , 2021, 18, e2100078.	3.0	7
23	Novel Method of Rebound Tailing Pulse (RTP) for Water Dissociation. <i>IEEE Transactions on Plasma Science</i> , 2021, 49, 2893-2900.	1.3	1
24	Low temperature plasma irradiation products of sodium lactate solution that induce cell death on U251SP glioblastoma cells were identified. <i>Scientific Reports</i> , 2021, 11, 18488.	3.3	20
25	Effects of Carbon Nanowalls (CNWs) Substrates on Soft Ionization of Low-Molecular-Weight Organic Compounds in Surface-Assisted Laser Desorption/Ionization Mass Spectrometry (SALDI-MS). <i>Nanomaterials</i> , 2021, 11, 262.	4.1	7
26	Inactivation mechanism of fungal spores through oxygen radicals in atmospheric-pressure plasma. <i>Japanese Journal of Applied Physics</i> , 2021, 60, 010503.	1.5	8
27	Insights into normothermic treatment with direct irradiation of atmospheric pressure plasma for biological applications. <i>Japanese Journal of Applied Physics</i> , 2021, 60, 010502.	1.5	10
28	Reduction in photon-induced interface defects by optimal pulse repetition rate in the pulse-modulated inductively coupled plasma. <i>Japanese Journal of Applied Physics</i> , 2021, 60, 010906.	1.5	2
29	On the Etching Mechanism of Highly Hydrogenated SiN Films by CF ₄ /D ₂ Plasma: Comparison with CF ₄ /H ₂ . <i>Coatings</i> , 2021, 11, 1535.	2.6	7
30	In-Liquid Plasma Synthesis of Nanographene with a Mixture of Methanol and 1-Butanol. <i>ChemNanoMat</i> , 2020, 6, 604-609.	2.8	4
31	Gas-phase and film analysis of hydrogenated amorphous carbon films: Effect of ion bombardment energy flux on sp ² carbon structures. <i>Diamond and Related Materials</i> , 2020, 104, 107651.	3.9	5
32	<i>In situ</i> surface analysis of an ion-energy-dependent chlorination layer on GaN during cyclic etching using Ar ⁺ ions and Cl radicals. <i>Journal of Vacuum Science and Technology A: Vacuum, Surfaces and Films</i> , 2020, 38, .	2.1	13
33	Reaction science of layer-by-layer thinning of graphene with oxygen neutrals at room temperature. <i>Carbon</i> , 2020, 170, 93-99.	10.3	5
34	Formation of spherical Sn particles by reducing SnO ₂ film in floating wire-assisted H ₂ /Ar plasma at atmospheric pressure. <i>Scientific Reports</i> , 2020, 10, 17770.	3.3	7
35	Small size gold nanoparticles enhance apoptosis-induced by cold atmospheric plasma via depletion of intracellular GSH and modification of oxidative stress. <i>Cell Death Discovery</i> , 2020, 6, 83.	4.7	46
36	Plasma Agriculture from Laboratory to Farm: A Review. <i>Processes</i> , 2020, 8, 1002.	2.8	125

#	ARTICLE	IF	CITATIONS
37	Influence of chamber pressure on the crystal quality of homo-epitaxial GaN grown by radical-enhanced MOCVD (REMOCVD). <i>Journal of Crystal Growth</i> , 2020, 549, 125863.	1.5	4
38	Non-thermal plasma-activated lactate solution kills U251SP glioblastoma cells in an innate reductive manner with altered metabolism. <i>Archives of Biochemistry and Biophysics</i> , 2020, 688, 108414.	3.0	20
39	Numerical simulations of stable, high-electron-density atmospheric pressure argon plasma under pin-to-plane electrode geometry: effects of applied voltage polarity. <i>Journal Physics D: Applied Physics</i> , 2020, 53, 265204.	2.8	23
40	Electronic properties and primary dissociation channels of fluoromethane compounds. <i>Japanese Journal of Applied Physics</i> , 2020, 59, SJJE02.	1.5	6
41	Steering of surface discharges on through-glass-vias combined with high-density nonequilibrium atmospheric pressure plasma generation. <i>Journal Physics D: Applied Physics</i> , 2020, 53, 435203.	2.8	1
42	Adjusted multiple gases in the plasma flow induce differential antitumor potentials of plasma-activated solutions. <i>Plasma Processes and Polymers</i> , 2020, 17, 1900259.	3.0	17
43	Interaction of oxygen with polystyrene and polyethylene polymer films: A mechanistic study. <i>Journal of Applied Physics</i> , 2020, 127, .	2.5	20
44	Synthesis of isolated carbon nanowalls via high-voltage nanosecond pulses in conjunction with CH ₄ /H ₂ plasma enhanced chemical vapor deposition. <i>Carbon</i> , 2020, 161, 403-412.	10.3	21
45	Electron spin resonance as a tool to monitor the influence of novel processing technologies on food properties. <i>Trends in Food Science and Technology</i> , 2020, 100, 77-87.	15.1	37
46	Roles of Atomic Nitrogen/Hydrogen in GaN Film Growth by Chemically Assisted Sputtering with Dual Plasma Sources. <i>ACS Omega</i> , 2020, 5, 26776-26785.	3.5	2
47	Characterization of a microsecond pulsed non-equilibrium atmospheric pressure Ar plasma using laser scattering and optical emission spectroscopy. <i>Plasma Science and Technology</i> , 2020, 22, 065404.	1.5	1
48	In-plane modification of hexagonal boron nitride particles via plasma in solution. <i>Applied Physics Express</i> , 2020, 13, 066001.	2.4	7
49	Dry Process. <i>Japanese Journal of Applied Physics</i> , 2020, 59, SJ0001.	1.5	0
50	Etching characteristics of PECVD-prepared SiN films with CF ₄ /D ₂ and CF ₄ /H ₂ plasmas at different temperatures. , 2020, , .		1
51	Numerical analysis of coaxial dielectric barrier helium discharges: three-stage mode transitions and internal bullet propagation. <i>Applied Physics Express</i> , 2020, 13, 086001.	2.4	6
52	Laser-induced-plasma-activated medium enables killing of HeLa cells. <i>Applied Physics Express</i> , 2020, 13, 106001.	2.4	0
53	Progress and perspectives in dry processes for emerging multidisciplinary applications: how can we improve our use of dry processes?. <i>Japanese Journal of Applied Physics</i> , 2019, 58, SE0803.	1.5	4
54	Atmospheric Pressure Plasma-Treated Carbon Nanowalls TM Surface-Assisted Laser Desorption/Ionization Time-of-Flight Mass Spectrometry (CNW-SALDI-MS). <i>Journal of Carbon Research</i> , 2019, 5, 40.	2.7	5

#	ARTICLE	IF	CITATIONS
55	Rapid thermal-cyclic atomic-layer etching of titanium nitride in CHF ₃ /O ₂ downstream plasma. <i>Journal Physics D: Applied Physics</i> , 2019, 52, 475106.	2.8	12
56	Self-limiting reactions of ammonium salt in CHF ₃ /O ₂ downstream plasma for thermal-cyclic atomic layer etching of silicon nitride. <i>Journal of Vacuum Science and Technology A: Vacuum, Surfaces and Films</i> , 2019, 37, .	2.1	24
57	Oxidative stress-dependent and -independent death of glioblastoma cells induced by non-thermal plasma-exposed solutions. <i>Scientific Reports</i> , 2019, 9, 13657.	3.3	48
58	Electrochemical Reaction in Hydrogen Peroxide and Structural Change of Platinum Nanoparticle-Supported Carbon Nanowalls Grown Using Plasma-Enhanced Chemical Vapor Deposition. <i>Journal of Carbon Research</i> , 2019, 5, 7.	2.7	3
59	Facile synthesis of SnO ₂ -graphene composites employing nonthermal plasma and SnO ₂ nanoparticles-dispersed ethanol. <i>Journal Physics D: Applied Physics</i> , 2019, 52, 175301.	2.8	8
60	Modifications of surface and bulk properties of magnetron-sputtered carbon films employing a post-treatment of atmospheric pressure plasma. <i>Japanese Journal of Applied Physics</i> , 2019, 58, SAAC07.	1.5	4
61	Simultaneous achievement of antimicrobial property and plant growth promotion using plasma-activated benzoic compound solution. <i>Plasma Processes and Polymers</i> , 2019, 16, 1900023.	3.0	19
62	Progress and perspectives in dry processes for leading-edge manufacturing of devices: toward intelligent processes and virtual product development. <i>Japanese Journal of Applied Physics</i> , 2019, 58, SE0804.	1.5	7
63	Review of methods for the mitigation of plasma-induced damage to low dielectric constant interlayer dielectrics used for semiconductor logic device interconnects. <i>Plasma Processes and Polymers</i> , 2019, 16, 1900039.	3.0	13
64	Rethinking surface reactions in nanoscale dry processes toward atomic precision and beyond: a physics and chemistry perspective. <i>Japanese Journal of Applied Physics</i> , 2019, 58, SE0801.	1.5	9
65	Progress and perspectives in dry processes for nanoscale feature fabrication: fine pattern transfer and high-aspect-ratio feature formation. <i>Japanese Journal of Applied Physics</i> , 2019, 58, SE0802.	1.5	24
66	Electronic properties and primarily dissociation channels of fluoroethane compounds. <i>Japanese Journal of Applied Physics</i> , 2019, 58, SEEF01.	1.5	5
67	Gene Expression of Osteoblast-like Cells on Carbon-Nanowall as Scaffolds during Incubation with Electrical Stimulation. <i>ACS Applied Bio Materials</i> , 2019, 2, 2698-2702.	4.6	6
68	Hetero-epitaxial growth of a GaN film by the combination of magnetron sputtering with Ar/Cl ₂ gas mixtures and a separate supply of nitrogen precursors from a high density radical source. <i>Japanese Journal of Applied Physics</i> , 2019, 58, SAAF04.	1.5	2
69	Chemical bonding structure in porous SiOC films ($\epsilon \approx 2.4$) with high plasma-induced damage resistance. <i>Micro and Nano Engineering</i> , 2019, 3, 1-6.	2.9	6
70	Laser-drilling formation of through-glass-via (TGV) on polymer-laminated glass. <i>Journal of Materials Science: Materials in Electronics</i> , 2019, 30, 10183-10190.	2.2	11
71	Plasma-activated solution alters the morphological dynamics of supported lipid bilayers observed by high-speed atomic force microscopy. <i>Applied Physics Express</i> , 2019, 12, 066001.	2.4	3
72	Effects of Ion Bombardment Energy Flux on Chemical Compositions and Structures of Hydrogenated Amorphous Carbon Films Grown by a Radical-Injection Plasma-Enhanced Chemical Vapor Deposition. <i>Journal of Carbon Research</i> , 2019, 5, 8.	2.7	1

#	ARTICLE	IF	CITATIONS
73	Effects of BCl ₃ addition to Cl ₂ gas on etching characteristics of GaN at high temperature. Journal of Vacuum Science and Technology B: Nanotechnology and Microelectronics, 2019, 37, 021209.	1.2	7
74	Effects of plasma shield plate design on epitaxial GaN films grown for large-sized wafers in radical-enhanced metalorganic chemical vapor deposition. Journal of Vacuum Science and Technology B: Nanotechnology and Microelectronics, 2019, 37, 031201.	1.2	4
75	Adhesion enhancement and amine reduction using film redeposited at the interface of a stack of plasma-enhanced CVD dielectrics for Cu/low- <i>k</i> interconnects. Japanese Journal of Applied Physics, 2019, 58, 020908.	1.5	2
76	Effect of electrical stimulation on proliferation and bone-formation by osteoblast-like cells cultured on carbon nanowalls scaffolds. Applied Physics Express, 2019, 12, 025006.	2.4	8
77	Polyethylene terephthalate (PET) surface modification by VUV and neutral active species in remote oxygen or hydrogen plasmas. Plasma Processes and Polymers, 2019, 16, 1800175.	3.0	26
78	Narrow free-standing features fabricated by top-down self-limited trimming of organic materials using precisely temperature-controlled plasma etching system. Japanese Journal of Applied Physics, 2019, 58, 020906.	1.5	4
79	Single-Step, Low-Temperature Simultaneous Formations and in Situ Binding of Tin Oxide Nanoparticles to Graphene Nanosheets by In-Liquid Plasma for Potential Applications in Gas Sensing and Lithium-Ion Batteries. ACS Applied Nano Materials, 2019, 2, 649-654.	5.0	8
80	Remotely floating wire-assisted generation of high-density atmospheric pressure plasma and SF ₆ -added plasma etching of quartz glass. Journal of Applied Physics, 2019, 125, 063304.	2.5	6
81	Simulation-aided design of very-high-frequency excited nitrogen plasma confinement using a shield plate. Journal of Vacuum Science and Technology B: Nanotechnology and Microelectronics, 2019, 37, .	1.2	2
82	Effects of 3D structure on electrochemical oxygen reduction characteristics of Pt-nanoparticle-supported carbon nanowalls. Journal Physics D: Applied Physics, 2019, 52, 105503.	2.8	5
83	Control of sp ² -C cluster incorporation of amorphous carbon films grown by H-radical-injection CH ₄ /H ₂ plasma-enhanced chemical vapor deposition. Japanese Journal of Applied Physics, 2019, 58, 030912.	1.5	8
84	Systematic diagnostics of the electrical, optical, and physicochemical characteristics of low-temperature atmospheric-pressure helium plasma sources. Journal Physics D: Applied Physics, 2019, 52, 165202.	2.8	21
85	Non-thermal plasma-activated medium modified metabolomic profiles in the glycolysis of U251SP glioblastoma. Archives of Biochemistry and Biophysics, 2019, 662, 83-92.	3.0	33
86	Pt nanoparticle-supported carbon nanowalls electrode with improved durability for fuel cell applications using C ₂ F ₆ /H ₂ plasma-enhanced chemical vapor deposition. Applied Physics Express, 2019, 12, 015001.	2.4	6
87	Liquid dynamics in response to an impinging low-temperature plasma jet. Journal Physics D: Applied Physics, 2019, 52, 075203.	2.8	15
88	A 65-nm CMOS Fully Integrated Analysis Platform Using an On-Chip Vector Network Analyzer and a Transmission-Line-Based Detection Window for Analyzing Circulating Tumor Cell and Exosome. IEEE Transactions on Biomedical Circuits and Systems, 2019, 13, 470-479.	4.0	13
89	Oxygen reduction reaction properties of nitrogen-incorporated nanographenes synthesized using in-liquid plasma from mixture of ethanol and iron phthalocyanine. Japanese Journal of Applied Physics, 2018, 57, 040303.	1.5	6
90	Cytotoxicity of cancer HeLa cells sensitivity to normal MCF10A cells in cultivations with cell culture medium treated by microwave-excited atmospheric pressure plasmas. Journal Physics D: Applied Physics, 2018, 51, 115401.	2.8	6

#	ARTICLE	IF	CITATIONS
91	Reduced HeLa cell viability in methionine-containing cell culture medium irradiated with microwave-excited atmospheric-pressure plasma. <i>Plasma Processes and Polymers</i> , 2018, 15, 1700200.	3.0	12
92	Facile fabrication of a poly(ethylene terephthalate) membrane filter with precise arrangement of through-holes. <i>Japanese Journal of Applied Physics</i> , 2018, 57, 037001.	1.5	3
93	Nanographene synthesis employing in-liquid plasmas with alcohols or hydrocarbons. <i>Japanese Journal of Applied Physics</i> , 2018, 57, 026201.	1.5	18
94	Electron impact ionization of perfluoro-methyl-vinyl-ether C ₃ F ₆ O. <i>Plasma Sources Science and Technology</i> , 2018, 27, 015009.	3.1	10
95	Free radical generation by non-equilibrium atmospheric pressure plasma in alcohol-water mixtures: an EPR-spin trapping study. <i>Journal Physics D: Applied Physics</i> , 2018, 51, 095202.	2.8	17
96	Rapid growth of micron-sized graphene flakes using in-liquid plasma employing iron phthalocyanine-added ethanol. <i>Applied Physics Express</i> , 2018, 11, 015102.	2.4	16
97	Nanographene synthesized in triple-phase plasmas as a highly durable support of catalysts for polymer electrolyte fuel cells. <i>Japanese Journal of Applied Physics</i> , 2018, 57, 045101.	1.5	11
98	Plasma-activated medium (PAM) kills human cancer-initiating cells. <i>Pathology International</i> , 2018, 68, 23-30.	1.3	50
99	Selective production of reactive oxygen and nitrogen species in the plasma-treated water by using a nonthermal high-frequency plasma jet. <i>Japanese Journal of Applied Physics</i> , 2018, 57, 0102B4.	1.5	22
100	Glioblastoma Cell Lines Display Different Sensitivities to Plasma-Activated Medium. <i>IEEE Transactions on Radiation and Plasma Medical Sciences</i> , 2018, 2, 99-102.	3.7	3
101	Dissociative properties of 1,1,1,2-tetrafluoroethane obtained by computational chemistry. <i>Japanese Journal of Applied Physics</i> , 2018, 57, 06JC02.	1.5	8
102	Real-time control of a wafer temperature for uniform plasma process. , 2018, , .		1
103	Temperature dependence on plasma-induced damage and chemical reactions in GaN etching processes using chlorine plasma. <i>Japanese Journal of Applied Physics</i> , 2018, 57, 06JD01.	1.5	3
104	Cell Deposition Microchip with Micropipette Control over Liquid Interface Motion. <i>Cell Medicine</i> , 2018, 10, 215517901773315.	5.0	1
105	Impact of helium pressure in arc plasma synthesis on crystallinity of single-walled carbon nanotubes. <i>Japanese Journal of Applied Physics</i> , 2018, 57, 06JF01.	1.5	0
106	Effects of gas residence time of CH ₄ /H ₂ on sp ² fraction of amorphous carbon films and dissociated methyl density during radical-injection plasma-enhanced chemical vapor deposition. <i>Japanese Journal of Applied Physics</i> , 2018, 57, 06JE03.	1.5	7
107	Effect of N ₂ /H ₂ plasma on GaN substrate cleaning for homoepitaxial GaN growth by radical-enhanced metalorganic chemical vapor deposition (REMOCVD). <i>AIP Advances</i> , 2018, 8, 115116.	1.3	4
108	Molecular mechanisms of non-thermal plasma-induced effects in cancer cells. <i>Biological Chemistry</i> , 2018, 400, 87-91.	2.5	43

#	ARTICLE	IF	CITATIONS
109	Reaction mechanisms between chlorine plasma and a spin-on-type polymer mask for high-temperature plasma etching. Japanese Journal of Applied Physics, 2018, 57, 106502.	1.5	1
110	Progress in nanoscale dry processes for fabrication of high-aspect-ratio features: How can we control critical dimension uniformity at the bottom?. Japanese Journal of Applied Physics, 2018, 57, 06JA01.	1.5	57
111	Elevated-temperature etching of gallium nitride (GaN) in dual-frequency capacitively coupled plasma of CH ₄ /H ₂ at 300–500 °C. Vacuum, 2018, 156, 219-223.	3.5	6
112	Cytotoxic effects of plasma-irradiated fullerene. Journal Physics D: Applied Physics, 2018, 51, 375401.	2.8	1
113	Low-autofluorescence fluoropolymer membrane filters for cell filtration. Japanese Journal of Applied Physics, 2018, 57, 06JF03.	1.5	5
114	New Hopes for Plasma-Based Cancer Treatment. Plasma, 2018, 1, 150-155.	1.8	35
115	Isotropic atomic level etching of tungsten using formation and desorption of tungsten fluoride. , 2018, , .		3
116	Investigation of effects of ion energies on both plasma-induced damage and surface morphologies and optimization of high-temperature Cl ₂ plasma etching of GaN. Japanese Journal of Applied Physics, 2017, 56, 026502.	1.5	13
117	Behavior of absolute densities of atomic oxygen in the gas phase near an object surface in an AC-excited atmospheric pressure He plasma jet. Applied Physics Express, 2017, 10, 036201.	2.4	8
118	Spatial profiles of interelectrode electron density in direct current superposed dual-frequency capacitively coupled plasmas. Journal Physics D: Applied Physics, 2017, 50, 155201.	2.8	12
119	Effects of •OH and •NO radicals in the aqueous phase on H ₂ O ₂ and •NO ₂ generated in plasma-activated medium. Journal Physics D: Applied Physics, 2017, 50, 155202.	2.8	73
120	Characteristics of optical emissions of arc plasma processing for high-rate synthesis of highly crystalline single-walled carbon nanotubes. Japanese Journal of Applied Physics, 2017, 56, 035101.	1.5	5
121	Bactericidal pathway of <i>Escherichia coli</i> in buffered saline treated with oxygen radicals. Journal Physics D: Applied Physics, 2017, 50, 155208.	2.8	24
122	Selective atomic-level etching using two heating procedures, infrared irradiation and ion bombardment, for next-generation semiconductor device manufacturing. Journal Physics D: Applied Physics, 2017, 50, 194001.	2.8	17
123	Intracellular-molecular changes in plasma-irradiated budding yeast cells studied using multiplex coherent anti-Stokes Raman scattering microscopy. Physical Chemistry Chemical Physics, 2017, 19, 13438-13442.	2.8	7
124	Temperature dependence of protection layer formation on organic trench sidewall in H ₂ /N ₂ plasma etching with control of substrate temperature. Japanese Journal of Applied Physics, 2017, 56, 076202.	1.5	4
125	Progress and prospects in nanoscale dry processes: How can we control atomic layer reactions?. Japanese Journal of Applied Physics, 2017, 56, 06HA02.	1.5	36
126	Hydrogen peroxide sensor based on carbon nanowalls grown by plasma-enhanced chemical vapor deposition. Japanese Journal of Applied Physics, 2017, 56, 06HF03.	1.5	28

#	ARTICLE	IF	CITATIONS
127	Spatial distributions of O, N, NO, OH and vacuum ultraviolet light along gas flow direction in an AC-excited atmospheric pressure Ar plasma jet generated in open air. <i>Journal Physics D: Applied Physics</i> , 2017, 50, 195202.	2.8	37
128	(Invited) Thermal Cyclic Atomic-Level Etching of Nitride Films: A Novel Way for Atomic-Scale Nanofabrication. <i>ECS Transactions</i> , 2017, 80, 3-14.	0.5	5
129	Thermally enhanced formation of photon-induced damage on GaN films in Cl ₂ plasma. <i>Japanese Journal of Applied Physics</i> , 2017, 56, 096501.	1.5	4
130	Cold atmospheric helium plasma causes synergistic enhancement in cell death with hyperthermia and an additive enhancement with radiation. <i>Scientific Reports</i> , 2017, 7, 11659.	3.3	31
131	Absolute density of precursor SiH ₃ radicals and H atoms in H ₂ -diluted SiH ₄ gas plasma for deposition of microcrystalline silicon films. <i>Applied Physics Letters</i> , 2017, 110, 043902.	3.3	4
132	Intracellular responses to reactive oxygen and nitrogen species, and lipid peroxidation in apoptotic cells cultivated in plasma-activated medium. <i>Plasma Processes and Polymers</i> , 2017, 14, 1700123.	3.0	23
133	High-durability catalytic electrode composed of Pt nanoparticle-supported carbon nanowalls synthesized by radical-injection plasma-enhanced chemical vapor deposition. <i>Journal Physics D: Applied Physics</i> , 2017, 50, 40LT01.	2.8	12
134	Growth of InN films by radical-enhanced metal organic chemical vapor deposition at a low temperature of 200 Å°C. <i>Japanese Journal of Applied Physics</i> , 2017, 56, 06HE08.	1.5	4
135	Lipid droplets exhaustion with caspases activation in HeLa cells cultured in plasma-activated medium observed by multiplex coherent anti-Stokes Raman scattering microscopy. <i>Biointerphases</i> , 2017, 12, 031006.	1.6	10
136	Dynamic analysis of reactive oxygen nitrogen species in plasma-activated culture medium by UV absorption spectroscopy. <i>Journal of Applied Physics</i> , 2017, 122, .	2.5	17
137	Crystallization of calcium oxalate dihydrate in a buffered calcium-containing glucose solution by irradiation with non-equilibrium atmospheric pressure plasma. <i>Journal of Applied Physics</i> , 2017, 122, 143301.	2.5	4
138	Surface roughening of photoresist after change of the photon/radical and ion treatment sequence. <i>Journal of Vacuum Science and Technology A: Vacuum, Surfaces and Films</i> , 2017, 35, 060606.	2.1	2
139	Dependence of absolute photon flux on infrared absorbance alteration and surface roughness on photoresist polymers irradiated with vacuum ultraviolet photons emitted from HBr plasma. <i>Japanese Journal of Applied Physics</i> , 2017, 56, 126503.	1.5	2
140	State of the art in medical applications using non-thermal atmospheric pressure plasma. <i>Reviews of Modern Plasma Physics</i> , 2017, 1, 1.	4.1	90
141	Electron behaviors in afterglow of synchronized dc-imposed pulsed fluorocarbon-based plasmas. <i>Japanese Journal of Applied Physics</i> , 2017, 56, 06HC03.	1.5	10
142	Reduction of chlorine radical chemical etching of GaN under simultaneous plasma-emitted photon irradiation. <i>Applied Physics Express</i> , 2017, 10, 086502.	2.4	3
143	Time Evolution Of Reactive Oxygen Nitrogen Species in Plasma-Activated Essential Media and Water. , 2017, , .		0
144	Dry Process. <i>Japanese Journal of Applied Physics</i> , 2017, 56, 06H001.	1.5	0

#	ARTICLE	IF	CITATIONS
145	Plasmatareatment induces blood clot formation; protein aggregation and hemolysis. , 2016, , .		0
146	Plasma Diagnostics. , 2016, , 117-141.		9
147	Effects of Radical Species on Structural and Electronic Properties of Amorphous Carbon Films Deposited by Radical-Injection Plasma-Enhanced Chemical Vapor Deposition. Plasma Processes and Polymers, 2016, 13, 730-736.	3.0	10
148	Cold plasma interactions with enzymes in foods and model systems. Trends in Food Science and Technology, 2016, 55, 39-47.	15.1	275
149	Real-time temperature monitoring of Si substrate during plasma processing and its heat-flux analysis. Japanese Journal of Applied Physics, 2016, 55, 01AB04.	1.5	6
150	Formation of a SiOF reaction intermixing layer on SiO ₂ etching using C ₄ F ₆ /O ₂ /Ar plasmas. Journal of Vacuum Science and Technology A: Vacuum, Surfaces and Films, 2016, 34, .	2.1	6
151	Rapid electron density decay observed by surface-wave probe in afterglow of pulsed fluorocarbon-based plasma. Japanese Journal of Applied Physics, 2016, 55, 080309.	1.5	15
152	Thermal cyclic etching of silicon nitride using formation and desorption of ammonium fluorosilicate. Applied Physics Express, 2016, 9, 106201.	2.4	30
153	Non-thermal atmospheric pressure plasma activates lactate in Ringerâ€™s solution for anti-tumor effects. Scientific Reports, 2016, 6, 36282.	3.3	167
154	Synthesis of calcium oxalate crystals in culture medium irradiated with non-equilibrium atmospheric-pressure plasma. Applied Physics Express, 2016, 9, 096201.	2.4	10
155	Red blood cell coagulation induced by low-temperature plasma treatment. Archives of Biochemistry and Biophysics, 2016, 605, 95-101.	3.0	93
156	Heliumâ€¢based cold atmospheric plasmaâ€¢induced reactive oxygen speciesâ€¢mediated apoptotic pathway attenuated by platinum nanoparticles. Journal of Cellular and Molecular Medicine, 2016, 20, 1737-1748.	3.6	43
157	Effects of assisted magnetic field to an atmospheric-pressure plasma jet on radical generation at the plasma-surface interface and bactericidal function. Plasma Sources Science and Technology, 2016, 25, 065005.	3.1	24
158	Impact of synergism of nitrite and hydrogen peroxide on cell survivals in Plasma-Activated-Medium (PAM). , 2016, , .		0
159	Effects of nitrogen on the apoptosis of and changes in gene expression in human lymphoma U937 cells exposed to argon-based cold atmospheric pressure plasma. International Journal of Molecular Medicine, 2016, 37, 1706-1714.	4.0	18
160	Main bactericidal factors of escherichia coli in solutions treated with neutral oxygen radicals. , 2016, , .		0
161	Microfluidic Transport Through Microsized Holes Treated by Nonequilibrium Atmospheric-Pressure Plasma. IEEE Transactions on Plasma Science, 2016, 44, 3060-3065.	1.3	1
162	(Invited) Control of Internal Plasma Parameters Toward Atomic Level Processing. ECS Transactions, 2016, 75, 21-24.	0.5	0

#	ARTICLE	IF	CITATIONS
163	Effect of gas residence time on near-edge X-ray absorption fine structures of hydrogenated amorphous carbon films grown by plasma-enhanced chemical vapor deposition. Japanese Journal of Applied Physics, 2016, 55, 040305.	1.5	4
164	Cell survival of glioblastoma grown in medium containing hydrogen peroxide and/or nitrite, or in plasma-activated medium. Archives of Biochemistry and Biophysics, 2016, 605, 102-108.	3.0	203
165	Computational study on SiH ₄ dissociation channels and H abstraction reactions. Japanese Journal of Applied Physics, 2016, 55, 07LD07.	1.5	2
166	Dry Process. Japanese Journal of Applied Physics, 2016, 55, 06H001.	1.5	0
167	Electronic properties of HBr, O ₂ and Cl ₂ used in Si etching. Japanese Journal of Applied Physics, 2015, 54, 06GA03.	1.5	1
168	Histological and Nuclear Medical Comparison of Inflammation After Hemostasis with Non-thermal Plasma and Thermal Coagulation. Plasma Processes and Polymers, 2015, 12, 1338-1342.	3.0	22
169	Plasma Blood Coagulation Without Involving the Activation of Platelets and Coagulation Factors. Plasma Processes and Polymers, 2015, 12, 1348-1353.	3.0	57
170	Silicon nitride etching performance of CH ₂ F ₂ plasma diluted with argon or krypton. Japanese Journal of Applied Physics, 2015, 54, 040303.	1.5	13
171	Robust characteristics of semiconductor-substrate temperature measurement by autocorrelation-type frequency-domain low-coherence interferometry. Japanese Journal of Applied Physics, 2015, 54, 01AB03.	1.5	10
172	Feedback Control System of Wafer Temperature for Advanced Plasma Processing and its Application to Organic Film Etching. IEEE Transactions on Semiconductor Manufacturing, 2015, 28, 515-520.	1.7	9
173	Estimation of activation energies for decomposition reaction of polymer by hydrogen radicals generated using hot-wire catalyzer. Thin Solid Films, 2015, 575, 17-20.	1.8	2
174	Hydrofluorocarbon ion density of argon- or krypton-diluted CH ₂ F ₂ plasmas: generation of CH ₂ F ⁺ and CHF ₂ ⁺ by dissociative-ionization in charge exchange collisions. Journal Physics D: Applied Physics, 2015, 48, 045202.	2.8	10
175	Quantitative clarification of inactivation mechanism of Penicillium digitatum spores treated with neutral oxygen radicals. Japanese Journal of Applied Physics, 2015, 54, 01AG05.	1.5	28
176	Study of the decomposition mechanism of PMMA-type polymers by hydrogen radicals. Thin Solid Films, 2015, 575, 12-16.	1.8	4
177	Experimental evidence of warm electron populations in magnetron sputtering plasmas. Journal of Applied Physics, 2015, 117, .	2.5	23
178	Plasma diagnostic approach for high rate nanocrystalline Si synthesis in RF/UHF hybrid plasmas using a PECVD process. Plasma Sources Science and Technology, 2015, 24, 025019.	3.1	25
179	Suppression of plasma-induced damage on GaN etched by a Cl ₂ plasma at high temperatures. Japanese Journal of Applied Physics, 2015, 54, 06GB04.	1.5	13
180	CF ₃ ⁺ fragmentation by electron impact ionization of perfluoro-propyl-vinyl-ethers, C ₅ F ₁₀ O, in gas phase. Japanese Journal of Applied Physics, 2015, 54, 040301.	1.5	10

#	ARTICLE	IF	CITATIONS
181	Plasma with high electron density and plasma-activated medium for cancer treatment. <i>Clinical Plasma Medicine</i> , 2015, 3, 72-76.	3.2	55
182	EPR-Spin Trapping and Flow Cytometric Studies of Free Radicals Generated Using Cold Atmospheric Argon Plasma and X-Ray Irradiation in Aqueous Solutions and Intracellular Milieu. <i>PLoS ONE</i> , 2015, 10, e0136956.	2.5	60
183	Decreased expression levels of cell cycle regulators and matrix metalloproteinases in melanoma from RET-transgenic mice by single irradiation of non-equilibrium atmospheric pressure plasmas. <i>International Journal of Clinical and Experimental Pathology</i> , 2015, 8, 9326-31.	0.5	1
184	Oxidation mechanism of <i>Penicillium digitatum</i> spores through neutral oxygen radicals. <i>Japanese Journal of Applied Physics</i> , 2014, 53, 010209.	1.5	33
185	Chemical reactions during plasma-enhanced atomic layer deposition of SiO ₂ films employing aminosilane and O ₂ /Ar plasma at 50 Å°C. <i>Japanese Journal of Applied Physics</i> , 2014, 53, 010305.	1.5	17
186	Effectiveness of plasma diagnostic in ultra high frequency and radio frequency hybrid plasmas for synthesis of silicon nitride film at low temperature. <i>Journal of Applied Physics</i> , 2014, 116, .	2.5	31
187	Effects of nitrogen plasma post-treatment on electrical conduction of carbon nanowalls. <i>Japanese Journal of Applied Physics</i> , 2014, 53, 040307.	1.5	14
188	Nanostructure modification to carbon nanowall surface employing hydrogen peroxide solution. <i>Japanese Journal of Applied Physics</i> , 2014, 53, 040305.	1.5	3
189	Hierarchical regrowth of flowerlike nanographene sheets on oxygen-plasma-treated carbon nanowalls. <i>Applied Physics Express</i> , 2014, 7, 046201.	2.4	5
190	Temporal changes in absolute atom densities in H ₂ and N ₂ mixture gas plasmas by surface modifications of reactor wall. <i>Japanese Journal of Applied Physics</i> , 2014, 53, 050301.	1.5	6
191	Spatiotemporal behaviors of absolute density of atomic oxygen in a planar type of Ar/O ₂ non-equilibrium atmospheric-pressure plasma jet. <i>Plasma Sources Science and Technology</i> , 2014, 23, 025004.	3.1	10
192	Density control of carbon nanowalls grown by CH ₄ /H ₂ plasma and their electrical properties. <i>Carbon</i> , 2014, 68, 380-388.	10.3	64
193	Recovery of atom density drift caused by change in reactor wall conditions by real-time autonomous control. <i>Journal Physics D: Applied Physics</i> , 2014, 47, 422002.	2.8	4
194	Plasma Medical Science for Cancer Therapy: Toward Cancer Therapy Using Nonthermal Atmospheric Pressure Plasma. <i>IEEE Transactions on Plasma Science</i> , 2014, 42, 3760-3764.	1.3	91
195	Epitaxial growth of GaN by radical-enhanced metalorganic chemical vapor deposition (REMOCVD) in the downflow of a very high frequency (VHF) N ₂ /H ₂ excited plasma – effect of TMG flow rate and VHF power. <i>Journal of Crystal Growth</i> , 2014, 391, 97-103.	1.5	20
196	Diagnostics of plasma-biological surface interactions in low pressure and atmospheric pressure plasmas. <i>International Journal of Modern Physics Conference Series</i> , 2014, 32, 1460318.	0.7	3
197	Formation of Nanoporous Features, Flat Surfaces, or Crystallographically Oriented Etched Profiles by the Si Chemical Dry Etching Using the Reaction of F ₂ + NO → F + FNO at an Elevated Temperature. <i>Journal of Physical Chemistry C</i> , 2013, 117, 20810-20818.	3.1	13
198	Inactivation effects of neutral reactive-oxygen species on <i>Penicillium digitatum</i> spores using non-equilibrium atmospheric-pressure oxygen radical source. <i>Applied Physics Letters</i> , 2013, 103, .	3.3	61

#	ARTICLE	IF	CITATIONS
199	Atomic Oxygen Etching from the Top Edges of Carbon Nanowalls. Applied Physics Express, 2013, 6, 095201.	2.4	9
200	Impact of hydrogen radical-injection plasma on fabrication of microcrystalline silicon thin film for solar cells. Journal of Applied Physics, 2013, 113, 033304.	2.5	10
201	Room-Temperature Si Etching in NO/F ₂ Gases and the Investigation of Surface Reaction Mechanisms. Journal of Physical Chemistry C, 2013, 117, 5118-5125.	3.1	7
202	Etching Enhancement Followed by Nitridation on Low-k SiOCH Film in Ar/C ₅ F ₁₀ O Plasma. Japanese Journal of Applied Physics, 2013, 52, 020204.	1.5	3
203	Effect of gas flow on transport of O (³ P _j) atoms produced in ac power excited non-equilibrium atmospheric-pressure O ₂ /Ar plasma jet. Journal Physics D: Applied Physics, 2013, 46, 464006.	2.8	22
204	A novel fast and flexible technique of radical kinetic behaviour investigation based on pallet for plasma evaluation structure and numerical analysis. Journal Physics D: Applied Physics, 2013, 46, 265201.	2.8	1
205	Surface roughness development on ArF-photoresist studied by beam-irradiation of CF ₄ plasma. Journal Physics D: Applied Physics, 2013, 46, 102001.	2.8	9
206	Highly Selective Etching of SiO ₂ over Si ₃ N ₄ and Si in Capacitively Coupled Plasma Employing C ₅ HF ₇ Gas. Japanese Journal of Applied Physics, 2013, 52, 016201.	1.5	18
207	High H Radical Density Produced by 1-m-Long Atmospheric Pressure Microwave Plasma System. Japanese Journal of Applied Physics, 2013, 52, 11NE01.	1.5	8
208	Wavelength Dependence of Photon-Induced Interface Defects in Hydrogenated Silicon Nitride/Si Structure during Plasma Etching Processes. Japanese Journal of Applied Physics, 2013, 52, 05ED01.	1.5	12
209	Photoluminescence Study of Plasma-Induced Damage of GaInN Single Quantum Well. Japanese Journal of Applied Physics, 2013, 52, 08JL09.	1.5	4
210	A High-Temperature Nitrogen Plasma Etching for Preserving Smooth and Stoichiometric GaN Surface. Applied Physics Express, 2013, 6, 056201.	2.4	23
211	Field Emissions from Organic Nanorods Armored with Metal Nanoparticles. Japanese Journal of Applied Physics, 2013, 52, 120203.	1.5	2
212	Dissociations of C ₅ F ₈ and C ₅ H ₇ F in Etching Plasma. Japanese Journal of Applied Physics, 2013, 52, 05EB02.	1.5	7
213	Development of the sputtering yields of ArF photoresist after the onset of argon ion bombardment. Journal of Applied Physics, 2013, 113, .	2.5	3
214	Surface loss probability of H radicals on silicon thin films in SiH ₄ /H ₂ plasma. Journal of Applied Physics, 2013, 113, .	2.5	6
215	Supercritical Fluid Deposition of High-Density Nanoparticles of Photocatalytic TiO ₂ on Carbon Nanowalls. Applied Physics Express, 2013, 6, 045103.	2.4	10
216	Rapid measurement of substrate temperatures by frequency-domain low-coherence interferometry. Applied Physics Letters, 2013, 103, 182102.	3.3	11

#	ARTICLE	IF	CITATIONS
217	Development of High-Density Nitrogen Radical Source for Low Mosaicity and High Rate Growth of InGaN Films in Molecular Beam Epitaxy. Japanese Journal of Applied Physics, 2013, 52, 021001.	1.5	5
218	A Development of Atmospheric Pressure Plasma Equipment and Its Applications for Treatment of Ag Films Formed from Nano-Particle Ink. Journal of Physics: Conference Series, 2013, 441, 012019.	0.4	8
219	Effect of Indirect Nonequilibrium Atmospheric Pressure Plasma on Anti-Proliferative Activity against Chronic Chemo-Resistant Ovarian Cancer Cells In Vitro and In Vivo. PLoS ONE, 2013, 8, e81576.	2.5	335
220	Surface morphology on high-temperature plasma-etched gallium nitride. Transactions of the Materials Research Society of Japan, 2013, 38, 325-328.	0.2	3
221	Direct current superposed dual-frequency capacitively coupled plasmas in selective etching of SiOCH over SiC. Journal Physics D: Applied Physics, 2012, 45, 025203.	2.8	27
222	Electron Spin Resonance (ESR) Observation of Radicals on Biological Organism Interacted with Plasmas. Materials Research Society Symposia Proceedings, 2012, 1469, 39.	0.1	0
223	Feature Profiles on Plasma Etch of Organic Films by a Temporal Control of Radical Densities and Real-Time Monitoring of Substrate Temperature. Japanese Journal of Applied Physics, 2012, 51, 016202.	1.5	12
224	Quantum Chemical Investigation of Si Chemical Dry Etching by Flowing NF_3 into N_2 Downflow Plasma. Japanese Journal of Applied Physics, 2012, 51, 026505.	1.5	9
225	Real time in situ electron spin resonance (ESR) study of surface reactoin on polymer interacted with plasma. , 2012, , .		0
226	Photoluminescence recovery by <i>in-situ</i> exposure of plasma-damaged n-GaN to atomic hydrogen at room temperature. AIP Advances, 2012, 2, .	1.3	12
227	Critical flux ratio of hydrogen radical to film precursor in microcrystalline silicon deposition for solar cells. Applied Physics Letters, 2012, 101, .	3.3	10
228	Anaysis of photoresist surface modified by fluorocarbon ions and radicals. , 2012, , .		0
229	Electron spin resonance (ESR) study of radicals on biological organism created by interaction with plasma. , 2012, , .		0
230	Individual Roles of Atoms and Ions during Hydrogen Plasma Passivation of Surface Defects on GaN Created by Plasma Etching. Japanese Journal of Applied Physics, 2012, 51, 111002.	1.5	8
231	Ultrahigh-Speed Synthesis of Nanographene Using Alcohol In-Liquid Plasma. Applied Physics Express, 2012, 5, 035101.	2.4	48
232	As-grown deep-level defects in n-GaN grown by metal-organic chemical vapor deposition on freestanding GaN. Journal of Applied Physics, 2012, 112, .	2.5	36
233	Quantum Chemical Investigation for Chemical Dry Etching of SiO_2 by Flowing NF_3 into H_2 Downflow Plasma. Japanese Journal of Applied Physics, 2012, 51, 016201.	1.5	12
234	Real-time <i>in situ</i> electron spin resonance measurements on fungal spores of <i>Penicillium digitatum</i> during exposure of oxygen plasmas. Applied Physics Letters, 2012, 101, 013704.	3.3	33

#	ARTICLE	IF	CITATIONS
235	Novel diffraction gratings fabricated by means of plasma nanotechnologies. Proceedings of SPIE, 2012, , .	0.8	0
236	Cell survival and proliferation signaling pathways are downregulated by plasma-activated medium in glioblastoma brain tumor cells. Plasma Medicine, 2012, 2, 207-220.	0.6	76
237	Decomposition Removal of the Polymers for Resist Material by the Hydrogen Radical Generated Using Tungsten Hot-Wire Catalyzer. Kobunshi Ronbunshu, 2012, 69, 266-273.	0.2	3
238	Vacuum Ultraviolet and Ultraviolet Radiation-Induced Effect of Hydrogenated Silicon Nitride Etching: Surface Reaction Enhancement and Damage Generation. Japanese Journal of Applied Physics, 2012, 51, 026201.	1.5	5
239	Feature Profiles on Plasma Etch of Organic Films by a Temporal Control of Radical Densities and Real-Time Monitoring of Substrate Temperature. Japanese Journal of Applied Physics, 2012, 51, 016202.	1.5	11
240	Quantum Chemical Investigation of Si Chemical Dry Etching by Flowing NF ₃ into N ₂ Downflow Plasma. Japanese Journal of Applied Physics, 2012, 51, 026505.	1.5	0
241	Individual Roles of Atoms and Ions during Hydrogen Plasma Passivation of Surface Defects on GaN Created by Plasma Etching. Japanese Journal of Applied Physics, 2012, 51, 111002.	1.5	2
242	Sticking coefficient of hydrogen radicals on ArF photoresist estimated by parallel plate structure in conjunction with numerical analysis. , 2011, , .		1
243	Dissociation Channels of c-C ₄ F ₈ to CF ₂ Radical in Reactive Plasma. Japanese Journal of Applied Physics, 2011, 50, 036203.	1.5	7
244	Synergistic Formation of Radicals by Irradiation with Both Vacuum Ultraviolet and Atomic Hydrogen: A Real-Time In Situ Electron Spin Resonance Study. Journal of Physical Chemistry Letters, 2011, 2, 1278-1281.	4.6	22
245	Plasma-Activated Medium Selectively Kills Glioblastoma Brain Tumor Cells by Down-Regulating a Survival Signaling Molecule, AKT Kinase. Plasma Medicine, 2011, 1, 265-277.	0.6	284
246	H ₂ /N ₂ plasma damage on porous dielectric SiOCH film evaluated by <i>in situ</i> film characterization and plasma diagnostics. Journal of Applied Physics, 2011, 109, .	2.5	27
247	Spatial Distributions of Electron, CF, and CF ₂ Radical Densities and Gas Temperature in DC-Superposed Dual-Frequency Capacitively Coupled Plasma Etch Reactor Employing Cyclic-C ₄ F ₈ /N ₂ /Ar Gas. Japanese Journal of Applied Physics, 2011, 50, 056101.	1.5	4
248	Behaviors of Absolute Densities of N, H, and NH ₃ at Remote Region of High-Density Radical Source Employing N ₂ –H ₂ Mixture Plasmas. Japanese Journal of Applied Physics, 2011, 50, 01AE03.	1.5	12
249	Impacts of CF ₂ ⁺ , CF ₂ ⁺ , CF ₃ ⁺ , and Ar Ion Beam Bombardment with Energies of 100 and 400 eV on Surface Modification of Photoresist. Japanese Journal of Applied Physics, 2011, 50, 08JE05.	1.5	5
250	Analysis of GaN Damage Induced by Cl ₂ /SiCl ₄ /Ar Plasma. Japanese Journal of Applied Physics, 2011, 50, 08JE03.	1.5	34
251	Laser Scattering Diagnosis of a 60-Hz Non-Equilibrium Atmospheric Pressure Plasma Jet. Applied Physics Express, 2011, 4, 026101.	2.4	33
252	Chemical bond modification in porous SiOCH films by H ₂ and H ₂ /N ₂ plasmas investigated by <i>in situ</i> infrared reflection absorption spectroscopy. Journal of Applied Physics, 2011, 110, .	2.5	30

#	ARTICLE	IF	CITATIONS
253	Hydrophobic treatment of organics against glass employing nonequilibrium atmospheric pressure pulsed plasmas with a mixture of CF ₄ and N ₂ gases. Journal of Applied Physics, 2011, 109, .	2.5	14
254	Inactivation of <i>Penicillium digitatum</i> Spores by a High-Density Ground-State Atomic Oxygen-Radical Source Employing an Atmospheric-Pressure Plasma. Applied Physics Express, 2011, 4, 116201.	2.4	71
255	Behaviors of Absolute Densities of N, H, and NH ₃ at Remote Region of High-Density Radical Source Employing N ₂ & H ₂ Mixture Plasmas. Japanese Journal of Applied Physics, 2011, 50, 01AE03.	1.5	8
256	Dissociation Channels of c-C ₄ F ₈ to CF ₂ Radical in Reactive Plasma. Japanese Journal of Applied Physics, 2011, 50, 036203.	1.5	2
257	Spatial Distributions of Electron, CF, and CF ₂ Radical Densities and Gas Temperature in DC-Superposed Dual-Frequency Capacitively Coupled Plasma Etch Reactor Employing Cyclic-C ₄ F ₈ /N ₂ /Ar Gas. Japanese Journal of Applied Physics, 2011, 50, 056101.	1.5	4
258	Analysis of GaN Damage Induced by Cl ₂ /SiCl ₄ /Ar Plasma. Japanese Journal of Applied Physics, 2011, 50, 08JE03.	1.5	40
259	Impacts of CF ⁺ , CF ₂ ⁺ , CF ₃ ⁺ , and Ar Ion Beam Bombardment with Energies of 100 and 400 eV on Surface Modification of Photoresist. Japanese Journal of Applied Physics, 2011, 50, 08JE05.	1.5	1
260	Measurement of Hydrogen Radical Density and Its Impact on Reduction of Copper Oxide in Atmospheric-Pressure Remote Plasma Using H ₂ and Ar Mixture Gases. Applied Physics Express, 2010, 3, 126101.	2.4	42
261	A new framework for performance prediction of advanced MOSFETs with plasma-induced recess structure and latent defect site. , 2008, , .		13
262	Enhancing Yield and Reliability by Applying Dry Organic Acid Vapor Cleaning to Copper Contact Via-Bottom for 32-nm Nodes and Beyond. , 2008, , .		1
263	Etching Damage in Diamond Studied Using an Energy-Controlled Oxygen Ion Beam. Japanese Journal of Applied Physics, 2007, 46, 60-64.	1.5	9
264	Structure of diamond surface defective layer damaged by hydrogen ion beam exposure. Diamond and Related Materials, 2006, 15, 703-706.	3.9	7
265	Defect creation in diamond by hydrogen plasma treatment at room temperature. Physica B: Condensed Matter, 2006, 376-377, 327-330.	2.7	5
266	Efficient Reduction of Standby Leakage Current in LSIs for Use in Mobile Devices. Japanese Journal of Applied Physics, 2006, 45, 3150-3153.	1.5	0
267	Surface reactions during etching of organic low-k films by plasmas of N ₂ and H ₂ . Journal of Applied Physics, 2006, 99, 083305.	2.5	40
268	In vacuo measurements of dangling bonds created during Ar-diluted fluorocarbon plasma etching of silicon dioxide films. Applied Physics Letters, 2005, 86, 264104.	3.3	20
269	Structural change in diamond by hydrogen plasma treatment at room temperature. Diamond and Related Materials, 2005, 14, 1939-1942.	3.9	18
270	Mass-analyzed CF _x ⁺ (x=1,2,3) ion beam study on selectivity of SiO ₂ -to-SiN etching and a-C:F film deposition. Journal of Applied Physics, 2005, 97, 053302.	2.5	55

#	ARTICLE	IF	CITATIONS
271	Etching yield of SiO ₂ irradiated by F ⁺ , CF _x ⁺ (x=1,2,3) ion with energies from 250 to 2000 eV. Journal of Vacuum Science and Technology A: Vacuum, Surfaces and Films, 2004, 22, 1166-1168.	2.1	73
272	Transitional change to amorphous fluorinated carbon film deposition under energetic irradiation of mass-analyzed carbon monofluoride ions on silicon dioxide surfaces. Journal of Vacuum Science and Technology A: Vacuum, Surfaces and Films, 2003, 21, L1-L3.	2.1	40
273	Surface and gas-phase observations of Ar-diluted c-C ₄ F ₈ plasma by using real-time infrared spectroscopy and planar laser-induced fluorescence. Journal of Applied Physics, 2003, 93, 1403-1408.	2.5	18
274	Vapor Treatment of Copper Surface Using Organic Acids. Materials Research Society Symposia Proceedings, 2003, 766, 3281.	0.1	7
275	Early-stage modification of a silicon oxide surface in fluorocarbon plasma for selective etching over silicon. Journal of Applied Physics, 2002, 91, 1661-1666.	2.5	11
276	In vacuo electron-spin-resonance study on amorphous fluorinated carbon films for understanding of surface chemical reactions in plasma etching. Applied Physics Letters, 2002, 81, 1773-1775.	3.3	9
277	Planar Laser-Induced Fluorescence of Fluorocarbon Radicals in Oxide Etch Process Plasma. Japanese Journal of Applied Physics, 2002, 41, 2207-2212.	1.5	5
278	Direct observation of surface dangling bonds during plasma process: chemical reactions during H ₂ and Ar plasma treatments. Thin Solid Films, 2002, 407, 139-143.	1.8	6
279	In-situ Time-Resolved Infrared Spectroscopic Study of Silicon Oxide Surface during Selective Etching over Silicon in Fluorocarbon Plasma. Japanese Journal of Applied Physics, 2000, 39, 6990-6995.	1.5	6
280	Asymmetric peak line shape of infrared dielectric function spectra for thermally grown silicon dioxide films. Journal of Applied Physics, 2000, 88, 7150-7156.	2.5	32
281	Contribution of interface roughness to the infrared spectra of thermally grown silicon dioxide films. Journal of Applied Physics, 1999, 85, 4076-4082.	2.5	24
282	Thickness-deconvolved structural properties of thermally grown silicon dioxide films. Journal of Applied Physics, 1999, 86, 3472-3474.	2.5	1
283	Analysis of native oxide growth process on an atomically flattened and hydrogen terminated Si (111) surface in pure water using Fourier transformed infrared reflection absorption spectroscopy. Journal of Vacuum Science and Technology A: Vacuum, Surfaces and Films, 1998, 16, 375-381.	2.1	12
284	Initial stage of native oxide growth on hydrogen terminated silicon (111) surfaces. Journal of Applied Physics, 1996, 79, 472-477.	2.5	58
285	Infrared Spectroscopy Study of Chemical Oxides Formed by a Sequence of RCA Standard Cleaning Treatments. Journal of the Electrochemical Society, 1996, 143, 2995-3000.	2.9	15
286	Effects of Dissolved Oxygen in HF Solution on Silicon Surface Morphology. Japanese Journal of Applied Physics, 1995, 34, 732-736.	1.5	19
287	An in-situ time-resolved infrared spectroscopic study of silicon dioxide (SiO ₂) surface during selective etching over silicon in fluorocarbon plasma. , 0, , .		0
288	Towards prevention and prediction of infectious diseases with virus sterilization using ultraviolet light and low-temperature plasma and bio-sensing devices for health and hygiene care. Japanese Journal of Applied Physics, 0, , .	1.5	2